PECVD Tube Furnace with 4 Channels Gas Delivery & Vacuum System OTF-1200X-50-4CLV-PE



Introduction

OTF-1200X-50-4CLV-PE is a CE certified compact PE-CVD tube furnace system (Plasma Enhanced Chemical Vapor Deposition), which consists of 500W RF plasma source, 2" O.D split tube furnace, 4 channels precision mass flow meter with gas mixing tank, and high quality mechanical pump.

The PE-CVD furnace is an ideal and affordable tool to deposit thin films or grow nano-wire from a gas state (vapor) to a solid state, and benefits:

- Lower temperature processing compared to conventional CVD.
- Film stress can be controlled by high/low frequency mixing techniques.
- Control over stoichiometry via process conditions.
- Offers a wide range of material deposition, including SiOx, SiOxNy and Amorphous silicon (a-Si:H) deposition.

Specification

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Split Tube furnace	• 1200°C max. working temperature.
	 30 segments programmable precision digital temperature controller.
	 440 mm length single heating zone and 150 mm length constant temperate zone 2"ODx1.7"IDx48" Length quartz tube.
	One pair of vacuum sealed flange with valves.
	 Input power: 208 – 240V AC input, single phase at max. 4KW
Plasma RF Power Supply	 Output Power: 5 -500W adjustable with ± 1% stability. RF frequency: 13.56 MHz ±0.005% stability. Reflection Power: 200W max. Matching: Automatic RF Output Port: 50 Ω, N-type, female
	 Noise: < 50dB. Cooling: Air cooling. Power: 208-240VAC, 50/60Hz
Vacuum Pump and valve	 Two stage mechanical vacuum pump installed with max. vacuum pressure 10⁻³ torr. KFD25 adaptor and stainless steel pipe are connected between pump and tube flange with precision ball valve. Digital vacuum pressure gauge and display are installed with the furnace. Optional: You choose a molecular pump from MTI to reach high vacuum upto 10⁻⁵ torr at extra cost
Mass Flow meters	 Four precision mass flow meters (0.02% accuracy) with digital display are installed on the bottom case to control gas flow rate automatically. MFC 1: Control range from 0~100 SCCM MFC 2&3: Control range from 0~200 SCCM MFC 4: Control range from 0~500 SCCM

	 One gas mixing tank is installed on bottom case with liquid release valve. 4 stainless steel needle valves is installed on left side of bottom case to control 4 type gases mixing manually. Gas inlet fitting: four 1/4NPS. Gas outlet fitting: four 1/4NPS.
Overall dimensions	 Furnace: 550 x 380 x 520mm 2 Bottom Mobile case: 1200 x 1200 mm. Net weight: 220 Lbs. Shipping weight: 350 lbs.
Warranty & Certificate	 One year limited warranty (Consumable parts such as processing tubes, o-rings and heating elements are not covered by the warranty, please order the replacement at related products below.) CE Certificate



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